(English follows Japanese)

M2-1-1 セルフ利用講習を申し込む(変更/キャンセルする)(セルフ利用講習基本情報登録)

1) セルフ利用講習を未受講の利用者・・p.1

2) セルフ利用講習を受講済みの利用者・・p.3

1) セルフ利用講習を未受講の利用者

①【予約管理】-【セルフ利用講習】-【セルフ利用講習基本情報登録】から設備左にマウスを移動しチェックボックス□にチェックを入れ、右上部「次へ」をクリック

| ≡ 7 | ◎ 設備一覧表示: | 0 | ③ 選択した行のアクション | | | | | | |
|--------------------|---------------------------------------------|--------------------------|---------------------------------------------------------|-----------------------|-------------------------------------------------------|-----------------------|--------------|-----------------------|------------------|
| すべて > ² | 学内(セルフ利用) = true.: | または、学外(セルフォ | 利用) = true > セルフ利用講習の要 | 否 = true | | | _ | | |
| <u> </u> | 設備表示名 | 所在建物 | 設備所属 | 設備担当者 | | | | | |
| | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 |
| | Light scattering system 光散乱検出 器システム | DAWN HELEOS II-MA-OFC | 636-JSIA040706: Particle size and particl | Wyatt Technology | DAWN HELEOS II • Optilab T-rEX • Dynapro Nan | Suzukakedai/すずか け台 | R1 Bldg./R1棟 | 分析部門 | 富田香苗 |
| | FIB-SEM System FIB-SEM複合装置 | JIB-4500-MA- OFC | 636- JSIA040316:Electromagnetic analysis | JEOL | JIB-4500 | Suzukakedai/すずか け台 | J1 Bldg./J1棟 | 分析部門 | 庄司大 |
| | Ellipsometer エリ プソメータ | EMC049 | | Gardner scientific | LSE-100 | Suzukakedai/すずか け台 | J1 Bldg./J1棟 | 電子物性評価 設備共用推進 体 | 飯野 裕明(設備担当 者) |
| | Ink jet printer for organic films and el | EMC060 | | Fuji Film | DMP2831 | Suzukakedai/すずか け台 | J1 Bldg./J1棟 | 電子物性評価 設備共用推進 体 | 飯野裕明(設備担当 者) |

※上部の検索で設備の絞り込みが可能です。例えば設備表示名について「*SEM」(*は半角)と検索した場合、設備表示名に「SEM」という文字列が含まれている設備が表示されます。また、より高度な絞り込み検索を行うには次頁の「Tips:設備を絞り込むには」をご確認ください。

(注意)セルフ利用する設備が表示されていない場合、セルフ利用者登録を必要としない設備です。セルフ利用を予約する(マニュアル M2-2-1)にお進みください。

Tips:●設備を絞り込むには

[1]上部の虫メガネのマークをクリックすると、絞り込み検索の入力欄が表示されます

| - | 2046-52 | 次へ検索の | 在建物 🔻 | 枝玄 | | | 44 | ۹ ۲ |
|----|---------|-----------------------------------------------------|----------------------------|-------|--------------------------------------|------------------------|----------|-----------------|
| 10 | Q | = 設備表示名 | 三設備名称 | ■カテゴリ | ≡ メーカー | 目目的 | ■所在キャンパス | = 所在建物 ▼ |
| | () | Scanning Electron Microscope(SEM): Facili | SU8020-FS-OFC | | Hitachi High- Tech Corporation | SU8020 | すずかけ台 | <u>G3년</u> |
| | () | X-ray Photoelectron Spectroscopy(XPS)- Ea | PHI VersaProbe 3-FS-OFC | | ULVAC-PHI, Inc. | PHI VersaProbe 3 | すすかけ台 | <u>G318</u> |
| | () | Baman Spectroscopy. Facility Station- Open | XploRA PLUS- FS-OFC | | HORIBA, Ltd. | XploRA PLUS | すすかけ台 | <u>G3地</u> |
| | (i) | Cryostat-2-Animal Research Facility: Open | CM30505-AR- OFC | | Leica | CM30505 | すずかけ台 | <u>B1 · B2標</u> |
| | (i) | Cryostat-1-Animal Research Facility- Open | HM525NX-AR- OFC | | РНС | HM525NX | <u> </u> | B1 · B2-C標 |
| | 0 | Multi-angle.light scattering.system- Mate | DAWN HELEOS II-MA-OFC | | Wyatt Technology | DAWN HELEOS II | <u> </u> | (空) |
| | (i) | MultiBeam System Materials Analysis Divi | JIB-4500-MA- OFC | | JEOL | JIB-4500 | すずかけ台 | (空) |
| | (j) | Scanning Electron Microscope (SEM): Mater | JSM-IT100-MA- OFC | | JEOL | JSM-IT100 | すずがけ台 | (空) |

[2]下のように設備表示名に「*電子顕微鏡」(*を最初に入れることで「電子顕微鏡」を含む設備が表示 されます)、所在キャンパスに「大岡山」と入力・Enter キーを押すと、大岡山キャンパスに設置された 電子顕微鏡が絞り込まれます。

| = | 設備一覧 | 次へ 検索 月 | 所在建物 ▼ | 検索 | | | 4 | • • • |
|---|------------|--------------------------------------------------------------------------------|-------------------------|--------|-------------------------------|-----------------|-----------|-------------|
| | Q | = 設備表示名 | ☰ 設備名称 | ≡ カテゴリ | ≡メーカー | ■型番 | = 所在キャンパス | ■ 所在建物 ▼ |
| | | "電子顕微鏡 | 検索 | 検索 | 検索 | 検索 | 大岡山 | 検索 |
| | (j) | Transmission Electron Microscope (TEM)- M | H7650 Zero.A- MA-OFC | | Hitachi High- Technologies | H7650 Zero.A | 大岡山 | (空) |
| | (j) | <u>Vacuum</u> <u>evaporator-</u> <u>Materials Analysis</u> <u>Div</u> | JEE-420T-MA- OFC | | JEOL | JEE-420T | 大岡山 | (空) |
| | (i) | Scanning Electron Microscope (SEM- EDS)-M | VE-9800-MA- OFC | | Keyence | VE-9800 | 大岡山 | (空) |
| | (i) | Field Emission Scanning Electron Microsc | JSM-7500F-MA- OFC | | JEOL | JSM-7500F | 大岡山 | (空) |
| | 選択し | た行のアクション… | ~ | | | | | (< < 1 |

[3]なお、設備表示名のように文字列が長くすべてが表示されていない場合は設備名の上にマウスポイン タを持っていくことですべて表示されます。

| | 没備一覧 | 次へ検索の | f在建物 🔻 | 検索 | | | | •• • 1 ~ |
|---------|-------------------------|--------------------------------------------------------------------------------|------------------------------|--------|-------------------------------|-----------------|-----------|------------------------|
| 8 Analy | smission ysis Divisi | Electron Microscope (on-Open Facility Cent | TEM)-Materials er / 透過型電子 | ≡ カテゴリ | ≡メーカー | ☰型番 | = 所在キャンパス | ☰ 所在建物 ▼ |
| 顕微 | 鎖-分析音 | 晴-オーノンノアシ! | リティセンター | 検索 | 検索 | 検索 | 大岡山 | 検索 |
| | (i) | <u>Transmission</u> <u>Electron</u> <u>Microscope (TEM)-</u> <u>M</u> | H7650 Zero.A- MA-OFC | | Hitachi High- Technologies | H7650 Zero.A | 大岡山 | (空) |
| | () | <u>Vacuum</u> <u>evaporator-</u> <u>Materials Analysis</u> Div | JEE-420T-MA- OFC | | JEOL | JEE-420T | 大岡山 | (空) |
| | (i) | Scanning Electron Microscope (SEM- EDS)-M | VE-9800-MA- OFC | | Keyence | VE-9800 | 大岡山 | (空) |
| | (j) | Field Emission Scanning Electron Microsc | JSM-7500F-MA- OFC | | JEOL | JSM-7500F | 大岡山 | (空) |
| | 選択し | た行のアクション… | ~ | | | | | 44 4 1 <i>·</i> |

●設備所属部門でグループ化して設備一覧を表示する

・「予約管理」-「セルフ利用講習」-「セルフ利用講習基本情報登録」を選択

「設備所属」の列の右側に表示されている3つの点をクリックし、「次でグループ化:設備所属」を選択

| 設備所属 | ⇒∩借収以考 | ≡ | ∇ | œ | 設備一覧 ビュー:Self | Use Training | 設備表示名 | ▼ ħ | 食索 |
|------------|------------------|-----|----------|-------|-------------------|--------------|-----------------|------|------|
| | ソート(昇順) | すべて | てゝ学 | 内(セ | ルフ利用) = True .または | ,学外(セルフ | /利用) = True > 1 | セルフ利 | 用講習な |
| 検索 | ソート(降順) | | | 0 | 机供考二点 | 記牒な物 | | + | |
| | グループ解除 | | | Q | 設備农东石 | 設備省が | | | 9 |
| 公析部門 | 次でグループ化:設備所属 | | | | 検索 | 検索 | | 検索 | |
| | 持方ニコ | • | 設備所 | 属: (玄 | 또) (2) | | | | |
| | | • | 设備所 | 属:先 | 端物理計測開発室(61) | | | | |
| 分析部門 | 円クラフ | | | | | | | | |
| 25 OTHER 5 | インタラクティブアナリシスの起動 | • | 受制用户方 | 庽:設 | 雷丁要作用作了(106) | | | | |
| () (stans | 構成 > | • 1 | 設備所 | 属:電 | 子物性評価設備共用推進 | 進体 (74) | | | |
| 分析部門 | インポート | • 1 | 设備所 | 属:フ | アシリティステーション | ン部門 (17) | | | |
| | エクスポート > | • 1 | 設備所 | 属:分 | 析部門 (60) | | | | |
| | | • | 設備所 | 属:オ | ープンファシリティセン | ンター (1) | | | |

(Tips ここまで)

②打ち合わせ(講習)希望日時に都合の良い時間帯を入力し、「送信」をクリック

| servicenow | | | | ナレッジ | カタログ | | | 冒買い物かご |
|------------|---------------------------------------|-------|---------------------|----------|------|-----|------------|--------|
| 7 | ホーム > 申込墓本情報登録 | | | | | 検索 | | ٩ |
| | 申込基本情報登録 ^{申込基本情報} 登録 | | | | | | <u>ن</u> د | |
| | 予約・申込種別 セルフ利用講員 | | | | | * | | |
| | 投偏名称 | 10517 | スタット-1-動物実験施設-オーブンコ | ファシリティセン | 19- | Ŧ., | | |
| | 打ち合わせ (講習) 希望日時 ^{希望開始日時1} | | 希望終了日時1 | | | | | |
| | 2023-02-02 10:00:00 | = | 2023-02-02 11:00:00 | | | = | | |
| | 希望開始日時2 | | 希望終了日時 2 | | | | | |
| | 2023-02-03 10:00:00 | = | 2023-02-03 11:00:00 | | | = | | |
| | 希望開始日時 3 | | 希望終了日時3 | | | | | |
| | 2023-02-01 10:00:00 | = | 2023-02-01 11:00:00 | | | = | | |
| | 連絡事項(概要及び希望日時・納期について) | | | | | | | |
| | | | | | | | | |

③(注意:セルフ利用講習が有料・無料で異なります)

(セルフ利用講習が<u>有料</u>の場合)申込の完了には講習に支払う予算の指定が必要です。申込の完了後に 予算情報登録画面が表示されます。予算詳細責任者等に予算使用の許可を得ている場合(パスコード取 得済もしくは予算利用者登録がされている場合)は、そのまま使用可能な予算情報を該当の予約に登録 してください。

予算詳細責任者等に予算使用の許可を得ていない場合は、許可を得た後(パスコード取得もしくは予算 利用者登録後)に、予算情報登録(パスコードの場合は <u>M2-1-2-1</u>、予算利用者登録の場合は <u>M2-1-2-</u> 2) にお進みください。予算情報登録後、システムからセルフ利用講習日時がメールで通知されますので、 ご受講ください。

(セルフ利用講習が<u>無料</u>の場合)申込は完了です。(申込の完了後に予算情報登録画面が表示されず確認 画面が表示される場合は、その時点で申込完了です。)後ほど、システムからセルフ利用講習日時がメー ルで通知されますので、ご受講ください。

2) セルフ利用講習を受講済みの利用者

①【予約管理】-【セルフ利用講習】-【セルフ利用講習基本情報登録】から設備左にマウスを移動しチェックボックス□にチェックを入れ、右上部「次へ」をクリック

| = ♡ | ◎ 設備一覧表示: | 0 |) 選択した行のアクション | | | | | | |
|----------|---------------------------------------------|--------------------------|------------------------------------------------------------------|-----------------------|-------------------------------------------------------|-----------------------|--------------|-----------------------|------------------|
| すべて > | 学内(セルフ利用) = true. | または、学外(セルフ፣ | 利用) = true > セルフ利用講習の要 | 좀 = true | | | | | |
| <u> </u> | 設備表示名 | 設備所属 | 設備担当者 | | | | | | |
| | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 | 検索 |
| | Light scattering system 光散乱検出 器システム | DAWN HELEOS II-MA-OFC | 636-JSIA0407 <u>06</u> :P article size and particl | Wyatt Technology | DAWN HELEOS II • Optilab T-rEX • Dynapro Nan | Suzukakedai/すずか け台 | R1 Bldg./R1棟 | 分析部門 | 富田香苗 |
| | FIB-SEM System FIB-SEM複合装置 | JIB-4500-MA- OFC | 636- JSIA040316:Electromagnetic analysis | JEOL | JIB-4500 | Suzukakedai/すずか け台 | J1 Bldg./J1棟 | 分析部門 | 庄司大 |
| | Ellipsometer エリ プソメータ | EMC049 | | Gardner scientific | LSE-100 | Suzukakedai/すずか け台 | J1 Bldg./J1棟 | 電子物性評価 設備共用推進 体 | 飯野 裕明(設備担当 者) |
| | Ink jet printer for organic films and el | EMC060 | | Fuji Film | DMP2831 | Suzukakedai/すずか け台 | J1 Bldg./J1棟 | 電子物性評価 設備共用推進 4 | 飯野 裕明(設備担当 者) |

※上部の検索で設備の絞り込みが可能です。例えば設備表示名について「*SEM」(*は半角)と検索した場合、設備表示名に「SEM」という文字列が含まれている設備が表示されます。また、より高度な絞り込み検索を行うには p.2 の「Tips:設備を絞り込むには」をご確認ください。

②打ち合わせ(講習)希望日時は未入力、連絡事項に「セルフ利用講習受講済み」と入力、「送信」をク リック

| service | now | | ナレッミ | ジ カタログ 要求 システムスラ | テータス 冒険い物かご ツ |
|---------|------------------------------------------|------------------------|--------------------------|------------------|---------------|
| | ホーム > 申込墓本情報登録 | | | 校索 | ٩ |
| | 申込基本情報登録 甲込基本情報登録 | | | | 送信 |
| | 予約、申込種別 | | | | |
| | セルフ利用調調 | | | ÷ . | / |
| | 設備名称 | | | | / |
| | Cryostat-1-Animal Research Facility-Open | Facility Center / クライオ | スタット-1-動物実験施設-オープンファシリティ | イセンター・・ | |
| | 打ち合わせ(講習)希望日時 | | | | |
| | 希望開始日時1 | | 希望終了日時1 | | |
| | YYYY-MM-DD HH:mm:ss | | YYYY-MM-DD HH:mm:ss | | |
| | 希望開始日時 2 | | 希望終了日時 2 | | |
| | YYYY-MM-DD HH:mm:ss | | YYYY-MM-DD HH:mm:ss | | |
| | 希望開始日時3 | | 希望終了日時3 | | |
| | YYYY-MM-DD HH:mm:ss | | YYYY-MM-DD HH:mm:ss | = | |
| | 連絡事項(概要及び希望日時・納期につい | ζ) | | | |
| | セルフ利用講習受講済み | | | / | |
| | | | | | |

③後ほど、セルフ利用者登録されるまでお待ちください(なお、セルフ利用者登録時にはシステムからメ ールが通知されます) ④【予約管理】-【セルフ利用講習】-【セルフ利用講習情報変更】から変更・キャンセルしたい申込にマウスを移動し左のチェックボックス□にチェックを入れ、上部「変更」または「キャンセル」をクリック
 ※変更の場合は④へ、キャンセルの場合は⑤へ

| = 予約一覧 予約番号 | ▼ 検索 | | | | | 0 | 選択した | 行のアクション | 変更 キャンセル |
|-------------|-----------------------------------|-------|-------|-----|---------------------|---------------------|------|---------|----------|
| 〇 〇 予約番号 | 設備名称 | 利用者氏名 | 目的 | 状況 | 予約開始日時 | 予約終了日時 | 予約日 | 予約開始コマ | 予約終了コマ |
| TASK0101810 | Circular Dichroism (CD) 円二色性分散計 | | セルフ利用 | 予約済 | 2024-07-22 14:30:00 | 2024-07-22 15:30:00 | | | |
| ④打ち合わせ | と (講習) 希望日時を | 修正し、 | 「送信」 | をク | リック | | | | |

| cenow | | | 要求 シ. | | 管理い物から |
|---------------------|-------|---------------------|-------|-----------------|--------|
| ホーム > 申込情報変更 | | | [| 検索 | |
| 申込情報変更 | | | | | 送信 |
| 申込番号 | | | | | |
| TASK0023301 | | | | | |
| 予約·申込種別 | | | | 200 201 - 15 | / |
| セルフ利用誘調 | | | | • | · |
| 設備名称 | | | | | |
| 0 XRD-Ookayama | | | | | |
| 打ち合わせ(講習)希望日時 | | | | _/ | |
| 希望開始日時1 | 8.7 L | 希望終了日時1 | | | |
| 2023-01-10 11:00:00 | = | 2023-01-10 12:00:00 | | = | |
| 希望開始日時2 | | 希望終了日時 2 | | | |
| YYYY-MM-DD HH:mm:ss | Ħ | YYYY-MM-DD HH:mm:ss | | = | |
| 希望附始日時 3 | | 希望終了日時3 | | | |
| YYYY-MM-DD HH:mm:ss | | YYYY-MM-DD HH:mm:ss | | = | |
| 連絡事項(根要及び希望日時・納用にて | 5017 | | | | |
| | | | | | |

(注意) システムから講習日時が通知された後の変更はできません。直接、設備担当者への連絡・調整を

お願いします。

⑤「送信」をクリックすると、申込がキャンセルされます。

| ホーム > 申込情報キャンセル | | | | 検索 | |
|------------------------------------------|----------------------|-------------------|--|-----|----|
| 申込情報キャンセル | | | | | 送信 |
| 申込番号 | | | | | |
| TASK0023301 | | | | | |
| 予約·申込種別 | | | | | |
| セルフ利用諸暦 | | | | * | |
| 設備名称 | | | | | |
| 0 XRD-Ookayama | | | | · · | |
| 打ち合わせ (講習) 希望日時 ^{希望附始日時1} | 希望終了日時 | ř 1 | | | |
| 2023-01-10 11:00:00 | 2023-01-10 | 12:00:00 | | | |
| 市 坐 时 / si 니 ㅋㅋ 2 YYYY-MM-DD HH:mm:ss | 新望時了日時 YYYY-MM-DI | 7 2 D HH:mm:ss | | | |
| 希望開始日時3 | 希望終了日時 | 3 | | | |
| YYYY-MM-DD HH:mm:ss | YYYY-MM-DI | D HH:mm:ss | | | |
| WARDER (WINDLIGHTER SHERE) | (| | | | |

(注意)システムから講習日時が通知された後のキャンセルはできません。直接、設備担当者への連絡・

調整をお願いします。

M2-1-1 Apply (or change, cancel) for Self-Use Training (Registering basic application information)

1)Users who have not yet taken the Self-Use training..... p.7

2) Users who have already taken the Self-Use training p.9

1)Users who have not yet taken the Self-Use training

[1] In [Reservation Management] - [Self-Use Reservation] - [Registering basic self-use information], check appropriate facility and click "Next" at the top.

| = 7 | 👳 Facility List View: Self U | Ise Training Facility dis | play name + Searc | :h | | | | Actions on selected Actions on selected Actions Actions | l rows 🗙 Next |
|-------------|----------------------------------------------|---------------------------|-------------------------------|-----------------------|----------------------------------------------------|-----------------------|--------------|---------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|------------------|
| All > Inter | rnal(self) = true .or. External(self) | = true > License = true | | | | | | | |
| <u> </u> | Facility display name | Facility name | Category | Maker | Model number | Campus | Building | Facility belong to | Own list |
| | Search | Search | Search | Search | Search | Search | Search | Search | Search |
| | Light scattering system 光 散乱検出器システム | DAWN HELEOS II- MA-OFC | 636- JSIA040706 | Wyatt Technology | DAWN HELEOS II • Optilab T-rEX • Dynapro Nan | Suzukakedai/ すずかけ台 | R1 Bldg./R1棟 | Materials Analysis Division | 富田香苗 |
| _ | F IB-SEM System FIB-SEM 複合装置 | JIB-4500-MA-OFC | 636- JSIA040316 | JEOL | JIB-4500 | Suzukakedai/ すずかけ台 | J1 Bldg,/J1棟 | Materials Analysis Division | 庄司大 |
| 0 | Ellipsometer エリプソメー タ | EMC049 | | Gardner scientific | LSE-100 | Suzukakedai/ すずかけ台 | J1 Bldg./J1棟 | EMC | 飯野裕明(設備 担当者) |
| | Ink jet printer for organic films and el | EMC060 | | Fuji Film | DMP2831 | Suzukakedai/ すずかけ台 | J1 Bldg,/J1棟 | EMC | 飯野 裕明(設備 担当者) |

Refined search is available. For example, a search for "*SEM" in the facility display name will display equipment that contains the string "SEM" in the facility display name.

For more advanced search refinement, please refer to the next page "Tips: How to Refine Facilities".

(Note) If the facility is not indicated, it is a facility that does not require self-user registration. Please proceed to "Make a reservation for self-use" (Manual M2-2-1).

Tips: - How to Refine Facilities

Click on the "magnifying glass" to display the input field for a narrowed-down search.

| E | Q | E Facility display name | E Facility name | Category | E Maker | Model number | Campus | Building | = |
|---|---|--------------------------------------------------|---------------------------|------------------------------------------------|-----------------------|---------------------------------------------------|-----------------------------------------------|------------------|------|
| • | _ | Search | Search | Search | Search | Search | Search | Search | Se |
| | 0 | listit scattering system: Materials Analys | DAWN HELEOS II-MA- OFC | 635-JSW040706-Particle size and particl | Wyatt Technology | DAWN HELEOS II - Optiab T eEX - Dynapro Nan | Suzakakedai//F <u>3⁴2/52/fi</u> | RI BOL RIP | Mat |
| | 0 | Arc Welding | Arc Welding | | | | (empty) | (empty) | |
| | 0 | MultiBeam System Materials Analysis Divi | JIB-4500-MA-OFC | 636. JSIA040316/flectromagnetic analysis | жо. | JIB-4500 | <u>Sundakedai/T</u> <u>IIIN761</u> | <u>月期读,用获</u> | Man |
| | 0 | Ellipsometer/エリプソメー 空 | EMCD49 | | Gardner scientific | LSE-100 | Sunkakodal/T T1N111 | <u>月846,71時</u> | EMO |
| | ١ | | (F7(用設備(3)(5)料 (其内型) | | | | Ookevame/大 回山 | (empty) | |
| | 0 | Inkiet printer for organic films and ol | EMCDED | | Fuji Film | DMP2831 | Sunikakedai/T 3723752 | <u>1846,08</u> | EM |
| | ٩ | Studie Frequency Tri Sapphire Laser/1876/1918 | EMCDIA | | DENSE | NER-110-015 | Sunskakedai/T T2N762 | 62.84(x,16288 | DM |
| | 0 | Scanning Electron Microscope (SEM)-2-Mat | JSM-ITTOD-MA-OFC | 635-JSIA040330:Scanning electron microscope | JECK | JSM-11100 | Sunkakedaj/T ThNtfit | <u>,1846,718</u> | Man |
| | 0 | abrasive outling machine-3- | L-BDP-DM-OFC | 323429:Other straight edge | dalwa | L-SEP | Sunkakedal/T | R2 Annes A/R2-A | Desi |

As shown below, enter "*Electron Microscope" in the Facility Display Name and "Ookayama" in the Location Campus and press the Enter key to narrow down the list of electron microscopes installed at the Ookayama Campus.

| = | Facility List | Next Search Facility | display name 🔻 Searc | h | | | 44 4 📃 | 1 to 2 of 2 🕨 |
|---------------------|---------------|---------------------------------------------|-------------------------|----------------------------------------------------|-------------------------------|----------------|-------------------------|------------------------------------|
| $\langle 0 \rangle$ | Q | = Eacility display pame | ■ Facility name | | ≡ Maker | ■ Model number | | Building |
| | | *Electron Microscope | Search | Search | Search | Search | Ookayama | Search |
| | (i) | Transmission Electron Microscope (TEM)-1 | H7650 Zero.A-MA- OFC | 636- JSIA040309:Transmission electron mic | Hitachi High- Technologies | H7650 Zero.A | <u>Ookayama/大</u> 回山 | <u>South Bldg, 7/</u> 大岡山南7号館 日 |
| | (j) | Field Emission Scanning Electron Microsc | JSM-7500F-MA-OFC | 636- JSIA040310:Scanning electron microscope | JEOL | JSM-7500F | <u>Ookayama/大</u> 岡山 | <u>South Bldg, 7/</u> 大同山南7号館 |
| | Actions o | en selected rows 🗸 🗸 | | | | | | 1 to 2 of 2 🕨 |

If the string is long, move the mouse pointer over the facility name to display the entire string.

| | 设備一覧 | 次へ検索の | 所在建物 ▼ | 検索 | | | - | • • • • • • |
|----------------|------------------------|--------------------------------------------------------------------------------|----------------------------|---------------|-------------------------------|-----------------|-----------|---------------|
| Trans Analy | smission sis Divisi | Electron Microscope (on-Open Facility Cent | TEM)-Materials er/透過型電子 | ■ カテゴリ | ≡ メーカー | ☰型番 | ≡ 所在キャンパス | ☰ 所在建物 ▼ |
| | 痕·分析肯 | 門・オーノンノアン! | レンター | 検索 | 検索 | 検索 | 大岡山 | 検索 |
| | (i) | <u>Transmission</u> <u>Electron</u> <u>Microscope (TEM)-</u> <u>M</u> | H7650 Zero.A- MA-OFC | | Hitachi High- Technologies | H7650 Zero.A | 大岡山 | (空) |
| | (j) | <u>Vacuum</u> <u>evaporator-</u> <u>Materials Analysis</u> <u>Div</u> | JEE-420T-MA- OFC | | JEOL | JEE-420T | 大岡山 | (空) |
| | (j) | Scanning Electron Microscope (SEM- EDS)-M | VE-9800-MA- OFC | | Keyence | VE-9800 | 大岡山 | (空) |
| | (j) | Field Emission Scanning Electron Microsc | JSM-7500F-MA- OFC | | JEOL | JSM-7500F | 大岡山 | (空) |
| | 選択し | た行のアクション… | ~ | | | | | 44 4 <u>1</u> |

- Display a list of facilities grouped by department

Select [Reservation Management] - [Self-Use Training] - [Registering Basic Self-Use Training Information], move the mouse to the relevant item to show the check box \Box , check the box to the left of the facilities you wish to use, and click "Next" at the top.

Click the three dots on the right side of the "Facility belong to" column and select "Group by Facility belong to"

| Facility belong to | Own list | | ≡ | ∇ | ę | Facility List View: Self U | lse Trai | ining | Facility display name | • |
|-------------------------------|-----------------------------|--------|-------|----------|--------|-------------------------------|----------|---------|-----------------------|---|
| | Sort (a to z) | | | | | | | | | _ |
| Search | Sort (z to a) | | All > | Intern | al(sel | f) = true .or. External(self) | = true | > Lice | nse = true | |
| | Ungroup | | | _ | | | | | | |
| Materials Analysis Division | Group By Facility belong to | | • | | Q | Facility display name | | Facilit | ty name | |
| | Bar Chart | \sim | | | | Search | | Sear | ch | 1 |
| Mataziala Azakusia Divisia | Pie Chart | | | | | | | | |) |
| Materials Analysis Divisio | Launch Interactive Analysis | | • | Facility | y belo | ong to: (empty) (2) | | | | |
| Materials Analysis Division | Configure > | | | Facility | y belo | ong to: AILAP (61) | | | | |
| | Import | | | | | | | | | |
| Materials Analysis Divisior - | Export > | | • | Facility | y belo | ng to: Design and Manuf | octuring | g Divis | ion (106) | |
| | | | • | Facility | y belo | ong to: EMC (74) | | | | |
| | | | • | Facility | y belo | ng to: Facility Station Div | ision (1 | .7) | | |

- Facility belong to: Materials Analysis Division (60)
- Facility belong to: Open Facility Center (1)

[2] Enter a convenient time for the desired meeting (training) and click "Submit.



[3] (Note: The process after the self-use training differs depending on whether the training is paid or free.)

(If the Self-Use training is fee-based) To complete the application, you must designate a budget to pay for the training. After completing the application, the budget information registration screen will be displayed. If you have permission to use the budget from the person in charge of budget details (if you have obtained a passcode or are registered as a budget user), please register the budget information that can be used as is for the relevant reservation.

If you have not obtained permission to use the budget from the person in charge of budget details, etc., please obtain permission (after obtaining a passcode or registering as a budget user) and then proceed to registering budget information ($\underline{M2-1-2-1}$ for a passcode, $\underline{M2-1-2-2}$ for registering as a budget user). After registering budget information, you will receive an e-mail notification from the system with the date and time of the Self-Use training.

(If the Self-Use Course is free) Your application is complete. (After completing your application, if the budget information registration screen does not appear but a confirmation screen does, your application is complete at that point.) You will receive an e-mail from the system with the date and time of the Self-Use training.

2) Users who have already taken the Self-Use training

[1] In [Reservation Management] - [Self-Use Reservation] - [Registering basic self-use information], check appropriate facility and click "Next" at the top.

| ≡ 7 | 👳 Facility List View: Self U | se Training Facility disp | olay name 🔹 Searc | h | | | | Actions on selected Actions Actions | rows Next |
|-------------|----------------------------------------------|---------------------------|-------------------------------|-----------------------|----------------------------------------------------|-----------------------|--------------|---------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|------------------|
| All > Inter | rnal(self) = true .or. External(self) | = true > License = true | | | | | | | |
| <u> </u> | Facility display name | Facility name | Category | Maker | Model number | Campus | Building | Facility belong to | Own list |
| | Search | Search | Search | Search | Search | Search | Search | Search | Search |
| | Light scattering system 光 散乱検出器システム | DAWN HELEOS II- MA-OEC | 636- JSIA040706 | Wyatt Technology | DAWN HELEOS II • Optilab T-rEX • Dynapro Nan | Suzukakedai/ すずかけ台 | R1 Bldg./R1棟 | Materials Analysis Division | 富田香苗 |
| _ | FI B-SEM System FIB-SEM 複合装置 | JIB-4500-MA-OFC | 636- JSIA040316 | JEOL | JIB-4500 | Suzukakedai/ すずかけ台 | J1 Bldg./J1棟 | Materials Analysis Division | 庄司大 |
| 0 | Ellipsometer エリプソメー タ | EMC049 | | Gardner scientific | LSE-100 | Suzukakedai/ すずかけ台 | J1 Bldg./J1棟 | EMC | 飯野 裕明(設備 担当者) |
| | Ink jet printer for organic films and el | EMC060 | | Fuji Film | DMP2831 | Suzukakedai/ すずかけ台 | J1 Bldg./J1棟 | EMC | 飯野 裕明(設備 担当者) |

Refined search is available. For example, a search for "*SEM" in the facility display name will display equipment that contains the string "SEM" in the facility display name.

For more advanced search refinement, please refer to the previous page "Tips: How to Refine Facilities".

[2] Do not enter the desired meeting (training) date and time. Enter "I have already taken the Self-Use training" in the " Contact information" field and click "Submit".



[3] Please wait until you are registered as a self-user. (When you are registered as a self-user, you will receive an e-mail from the system.

Change or Cancellation of Application

[3] In [Reservation Management] – [Self-Use Training] – [Change self-use training information], Move the mouse to the relevant item to show the check box \Box , check appropriate application and click "Change (proceed to [4])" or "Cancel (proceed to [5])" at the top.

| ≡ Res | ervation List Reservation n | umber - Search | | | | | 0 | Actions on selected rows | Change | Cancel |
|-------|-----------------------------|------------------------------------------|-----------|---------|---------------------|-----------------------------|---------------------------|--------------------------|------------------|--------|
| _ Q | Reservation number | Facility name | Opened by | Purpose | State | Reservation start date time | Reservation end date time | Reservation date | Start time block | End |
| | TASK0101810 | Circular Dichroism (CD) 円二色性分 散計 | 20,885 | Selfuse | Already reserved | 2024-07-22 14:30:00 | 2024-07-22 15:30:00 | | | |

[4] Modify a convenient time for the desired meeting (training) and click "Submit.

| Home > Change application information Change application information Change the application information Change the application information Number TASK0053911 Application type Self-Use Training Facility name ● F72.hH194805 Desired and time 1 Desired and time 1 Desired and time 1 Desired and time 2 Desired and time 2 YMY-MM-DD HH:rm:00 YMY-MM-DD HH:rm:00 YMY-MM-DD HH:rm:00 | information Search Catalog Cion information on | vicenow | Knowledge | Catalog Re | | System Status | Ì≓Ca |
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| Change application information Change the application information Number TASK0053911 Application type SetHUse Treining • • Facility name • Facility name • Facility name • Facility name • Facility name • Facility at date and time 1 2024-04-06 10:00:00 * Desired end date and time 1 2024-04-06 10:00:00 * Desired end date and time 2 • WYK-MM-DD HH.mm:00 * WYK-MM-DD HH.mm:00 * | time | Home > Change application information | | | Search | h Catalog | |
| Number TASK0055911 Application type Self-Use Training * Facility name | time Desired and date and time 1 Desired and date and time 2 Desired and date and time 2 Desired and date and time 3 Desired and date and time 3 WYYKMM-DD HH:rmm:00 | Change application inform Change the application information | ation | | | sut | omit |
| TASK0053911 Application type Self-Use Training * Facility name * Image: Self-Use Training * Pacility name * Image: Self-Use Training * Meeting desired date and time * Desired start date and time 1 Desired end date and time 1 2024-04-06 10:00:00 Image: Self-Use Control of Control | time Desired end date and time 1 Desired end date and time 1 Desired end date and time 2 Desired end date and time 2 Desired end date and time 3 | Number | | | | | |
| Application type SelFUse Training SelFUse Training Pacifity name Image: SelFUse Training Image: SelFUse T | | TASK0053911 | | | | | |
| Self-Use Training * Facility name * Image: Self-Self-Self-Self-Self-Self-Self-Self- | v time Desired end date and time 1 2024-04-06 12:00:50 Desired end date and time 2 Desired end date and time 2 Desired end date and time 3 WYYK-MM-DD HH-mm:00 VYYK-MM-DD HH-mm:00 | Application type | | | | | |
| Facility name Image: Second | time Desired end date and time 1 Equivalent time 1 Desired end date and time 2 Equivalent date and time 2 Desired end date and time 3 Equivalent time 3 Equi | Self-Use Training | | | Ψ. | | |
| ● FR NHSHR05 • Meeting desired date and time Desired and time 1 Desired start date and time 1 2024-04-06 12:00:00 2024-04-06 10:00:00 ■ Desired start date and time 2 Desired end date and time 2 VYY-MM-DD HH:mm:00 ■ | time Desired end date and time 1 Desired end date and time 1 Desired end date and time 2 Desired end date and time 2 Desired end date and time 3 Desired end date and time | Facility name | | | | | |
| Meeting desired date and time Desired start date and time 1 2024-04-06 10:00:00 2024-04-06 12:00:00 Desired start date and time 2 VYY-MM-DD HH:mm:00 Pesired start date and time 3 Desired end date and time 3 VYY-MM-DD HH:mm:00 YYY-MM-DD HH:mm:00 | time Desired end date and time 1 Desired end date and time 1 Desired end date and time 2 Desired end date and time 2 Desired end date and time 3 Desired end date and time 3 WYY-MM-DD HH:mm:00 | テスト用設備05 | | | · · | | |
| Desired start date and time 1 Desired end date and time 1 2024-04-06 10:00:00 2024-04-06 12:00:00 Desired start date and time 2 Desired end date and time 2 </td <td>Desired end date and time 1 Desired end date and time 2 Desired end date and time 2 Desired end date and time 3 Desired end date and time 3 PryryAMM-DD HH:mm:00</td> <td>Meeting desired date and time</td> <td></td> <td></td> <td></td> <td></td> <td></td> | Desired end date and time 1 Desired end date and time 2 Desired end date and time 2 Desired end date and time 3 Desired end date and time 3 PryryAMM-DD HH:mm:00 | Meeting desired date and time | | | | | |
| 2024-04-06 10:00:00 Image: Constraint of the | Image: Second | Desired start date and time 1 | Desired end date and time 1 | | | γ | |
| Desired start date and time 2 Desired end date and time 2 YYYY-MM-DD HH:mm:00 Image: Comparison of the | Desired end date and time 2 Image: Desired end date and time 2 VYYY-MM-DD HH:rmm:00 Image: Desired end date and time 3 Image: Desired end date and time 3 Image: Desired end date and time 3 | 2024-04-06 10:00:00 | 2024-04-06 12:00:00 | | | | |
| YYYY-MM-DD HH:mm:00 Image: Constraint of the second s | Image: WYY-MM-DD HH:mm:00 Image: WYY-MM-DD HH:mm:00 Image: Desired end date and time 3 Image: WYY-MM-DD HH:mm:00 | Desired start date and time 2 | Desired end date and time 2 | | | | |
| Desired start date and time 3 Desired end date and time 3 YYYY-MM-DD HH:mm:00 Image: WYYY-MM-DD HI:mm:00 Image: WYYY-MM-DD HI:mm:00< | Desired end date and time 3 | YYYY-MM-DD HH:mm:00 | YYYY-MM-DD HH:mm:00 | | = | | |
| YYYY-MM-DD HH:mm:00 Image: Comparison of the | VYYY-MM-DD HH:mm:00 | Desired start date and time 3 | Desired end date and time 3 | | | | |
| | | YYYY-MM-DD HH:mm:00 | YYYY-MM-DD HH:mm:00 | | # | | |
| Contact information | | Contact information | | | | | |

(Note) Once the date and time of the training have been notified by the system, changes cannot

be made. Please contact the facility owner.

[5] Click "Submit" to cancel the application.

| rvicenow | Knowledge | Catalog | Requests | System Status | ` ≓ Cart |
|-------------------------------|-----------------------------|---------|----------|---------------|-----------------|
| Home > Cancel application | | | Searc | h Catalog | |
| Cancel application | | | | | |
| Cancel the application | | | | Sul | bmit |
| Number | | | | | |
| TASK0053911 | | | | | |
| Application type | | | | | |
| Self-Use Training | | | Ψ. | | |
| Facility name | | | | | |
| ● テスト用設備05 | | | Ψ. | | |
| Meeting desired date and time | | | | | |
| Desired start date and time 1 | Desired end date and time 1 | | | | |
| 2024-04-06 10:00:00 | 2024-04-06 12:00:00 | | | | |
| Desired start date and time 2 | Desired end date and time 2 | | | | |
| | | | | | |
| Desired start date and time 3 | Desired end date and time 3 | | | | |
| | | | | | |
| Contact information | | | | | |
| | | | | | |

(Note) Once the date and time of the training have been notified by the system, changes cannot

be made. Please contact the facility owner.